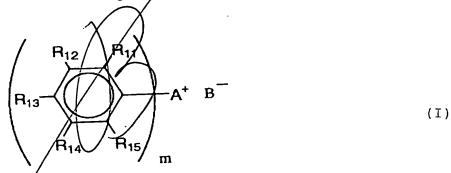


WHAT IS CLAIMED IS:

- 1. A positive radiation-sensitive composition comprising:
  - (a) a desin whose solubility in an alkali developer increases by the action of an acid;
- (b) a compound that generates a carboxylic acid having a molecular weight of 100 or less upon irradiation with an actinic ray or a radiant ray;
  - (c) a surfactant; and
  - (d) a solvent.
- 2. The positive radiation-sensitive composition as claimed in claim 1, which further comprises (b') a compound that generates a sulfonic acid upon irradiation with an actinic ray or a radiant ray.
- 3. The positive radiation-sensitive composition as claimed in claim 1, wherein the compound (b) is a compound represented by the following formula (I):



wherein  $R_{11}$ ,  $R_{12}$ ,  $R_{13}$ ,  $R_{14}$  and  $R_{15}$  each independently represents a hydrogen atom, a straight chain, branched or cyclic alkyl

group, a straight chain, branched or cyclic alkoxyl group, a hydroxyl group, a halogen atom, or  $-S-R_0$ ;  $R_0$  represents a straight chain, branched or cyclic alkyl group, or an aryl group;  $A^+$  represents  $S^+$  or  $I^+$ ;  $B^-$  represents  $CH_3COO^-$ ,  $C_2H_5COO^-$  or  $C_3H_7COO^-$ ; and m represents 2 or 3.

4. The positive radiation-sensitive composition as claimedinclaim1, wherein the resin (a) has an acid-decomposable group represented by the following formula (II):

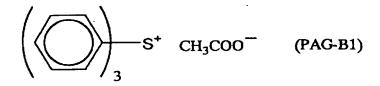
$$--O-C-O-(CH_2)_n-W$$

wherein  $R_1$  represents an alkyl group having from 1 to 4 carbon atoms; W represents an amino group, an ammonium group, a mercapto group, a substituted or unsubstituted aryl group, a substituted or unsubstituted cycloalkyl group, or an organic group containing (i) at least one atom selected from the group consisting of an oxygen atom, a nitrogen atom, a sulfur atom, a phosphorus atom and a silicon atom, and (ii) at least one carbon atom; and n represents a natural number of from 1 to 4.

5. The positive radiation-sensitive composition as claimed in claim 1, wherein the resin (a) is a resin in which phenolic hydroxyl groups in an alkali-soluble resin are at

least partly protected with the acid-decomposable group represented by the formula (II).

- 6. The positive radiation-sensitive composition as claimed in claim 1, which further comprises an organic basic compound.
- 7. The positive radiation-sensitive composition as claimed in claim 1 , wherein the compound (b) is at least one compound selected from the group consisting of the following (PAG-B1) to ( $\dot{P}AG-B6$ ):



$$\begin{pmatrix} & & \\ &$$

$$S^{+} \quad \text{n-C}_{3}H_{7}COO^{-} \quad \text{(PAG-B3)}$$

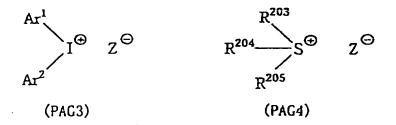
$$\begin{array}{c} \begin{array}{c} \\ \\ \end{array} \begin{array}{c} \\ \end{array} \end{array} \begin{array}{c} \\ \end{array} \end{array} \begin{array}{c} \\ \end{array} \end{array} \begin{array}{c} \\ \end{array} \begin{array}{c}$$

$$\begin{pmatrix} \bigcirc \\ 2 \end{pmatrix}_{2}^{+} C_{2}H_{5}COO^{-}$$
 (PAG-B5)

8. The positive radiation-sensitive composition as claimed in claim 7, wherein the compound (b) is at least one compound selected from the group consisting of the above (PAG-B1) and (PAG-B4):

9. The positive radiation sensitive composition as claimed in claim 1, which contains the compound (b) in an amount of from 1 to 20 wt% based on the solid contents.

10. The positive radiation-sensitive composition as claimed in claim 2, wherein the compound (b') is a compound represented by the following formula (PAG3), (PAG4) or (PAG6):



$$R^{206}$$
-SO<sub>2</sub>-O-N A
(PAG6)

• • •

wherein  $Ar^1$  and  $Ar^2$  each independently represents a substituted or unsubstituted aryl group;  $R^{203}$ ,  $R^{204}$  and  $R^{205}$  each independently represents a substituted or unsubstituted alkyl or aryl group;  $R^{206}$  represents a substituted or unsubstituted alkyl or aryl group; A represents a substituted or unsubstituted alkylene , alkenylene or arylene group.

- 11. The positive radiation-sensitive composition as claimed in claim 2, which contains the compound (b') in an amount of from 1 to 20 wt% based on the solid contents.
- 12. The positive radiation-sensitive composition as claimed in claim 4, wherein W of said formula (II) is a group represented by the following formula:

$$-O-C-R_2$$
  $-OR_2$   $-CH(COOR_2)_2$ 
 $-C(COOR_2)_3$   $-CH_2COOR_2$   $-N(COOR_2)_2$ 
 $-CH(CONHR_2)_2$   $-C(CONHR_2)_3$   $-CH_2CONHR_2$ 
 $-N(CONHR_2)_2$ 
 $-N(CONHR_2)_2$ 
 $-CHO$   $-R_4$ 
 $-CHO$   $-R_4$ 

wherein R₂ represents a hydrogen atom, a straight chain, branched

\* i

or cyclic alkyl group having from 1 to 6 carbon atoms, a straight chain, branched or cyclic alkenyl group having from 2 to 6 carbon atoms, a substituted or unsubstituted aryl group, or a substituted or unsubstituted aralkyl group; R<sub>3</sub> represents a hydrogen atom, a straight chain, branched or cyclic alkyl group having from 1 to 6 carbon atoms, a straight chain, branched or cyclic alkoxyl group having from 1 to 6 carbon atoms, a halogen atom, a nitro group, an amino group, a hydroxyl group, or a cyano group; R<sub>4</sub> represents a substituted or unsubstituted aryl group, or a substituted or unsubstituted cycloalkyl group having from 3 to 15 carbon atoms; m represents a natural number of from 1 to 4.

- 13. The positive radiation-sensitive composition as claimed in claim 4, wherein the resin (a) is a resin in which 5 to 45 mol% of an entire phenolic hydroxyl groups in an alkali-soluble resin are protected with an acid-decomposable group represented by the formula (II).
- 14. The positive radiation-sensitive composition as claimed in claim 1, wherein the resin (a) has a weight average molecular weight of from 3,000 to 80,000.
- 15. The positive radiation-sensitive composition as claimed in claim 1, wherein the surfactant (c) contains at least one of a fluorine atom and a silicon atom.